

(19) World Intellectual Property Organization  
International Bureau



(43) International Publication Date  
8 February 2007 (08.02.2007)

PCT

(10) International Publication Number  
**WO 2007/015712 A1**

(51) International Patent Classification:  
**G01R 1/067** (2006.01)

(74) Agents: FINKEL, Evan et al.; Pillsbury Winthrop Shaw  
Pittman LLP, Suite 2800, 725 South Figueroa Street, Los  
Angeles, CA 90017 (US).

(21) International Application Number:  
PCT/US2005/041665

(81) Designated States (unless otherwise indicated, for every  
kind of national protection available): AE, AG, AL, AM,  
AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN,  
CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI,  
GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE,  
KG, KM, KN, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV,  
LY, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI,  
NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG,  
SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US,  
UZ, VC, VN, YU, ZA, ZM, ZW.

(22) International Filing Date:  
18 November 2005 (18.11.2005)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:  
11/194,720 1 August 2005 (01.08.2005) US

(71) Applicant (for all designated States except US): **TOUCH-  
DOWN TECHNOLOGIES, INC.** [US/US]; 5188 Com-  
merce Drive, Baldwin Park, CA 91706 (US).

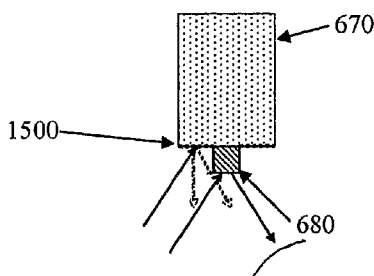
(84) Designated States (unless otherwise indicated, for every  
kind of regional protection available): ARIPO (BW, GH,  
GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM,  
ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM),  
European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI,  
FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT,  
RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA,  
GN, GQ, GW, ML, MR, NE, SN, TD, TG).

(72) Inventors: **ISMAIL, Salleh**; 14031 Christian Barrett  
Drive, Moorpark, CA 93021 (US). **TEA, Nim**; 190  
City Boulevard West, #301, Orange, CA 92868 (US).  
**HSU, Yang**; 1820 San Marino Avenue, San Marino, CA  
91108 (US). **TANG, Weilong**; 9141 Arcadia Avenue,  
San Gabriel, CA 91775 (US). **GARABEDIAN, Raffi**;  
510 North Alta Vista Avenue, Monrovia, CA 91016 (US).  
**KHOO, Melvin**; 9100 Duarte #241, San Gabriel, CA  
91775 (US).

**Published:**  
— with international search report

For two-letter codes and other abbreviations, refer to the "Guid-  
ance Notes on Codes and Abbreviations" appearing at the begin-  
ning of each regular issue of the PCT Gazette.

(54) Title: POST AND TIP DESIGN FOR A PROBE CONTACT



(57) Abstract: The present invention relates to a microfabricated tip (680) and post structure (670) comprising a post having a rough top surface (1500) that diffuses incident light and a cross-section, and a tip, lithographically plated on the rough top surface of the post, having a smooth reflective surface appropriate for automatic vision recognition, and having a cross-section that is less than the cross-section of the post.

WO 2007/015712 A1

## POST AND TIP DESIGN FOR A PROBE CONTACT

### BACKGROUND

The present invention relates generally to the testing of semiconductor chips, and specifically to the design of probe contactors for such testing prior to packaging.

Typically, semiconductor chips are tested to verify that they function appropriately and reliably. This is often done when the semiconductor devices are still in wafer form, that is, before they are diced from the wafer and packaged. This allows the simultaneous testing of many chips at a single time, creating considerable advantages in cost and process time compared to testing individual chips once they are packaged. If chips are found to be defective, then when the chips are diced from the wafer, the defective ones can be discarded and only the reliable chips are packaged. It is an axiom then that the larger a wafer that may be reliably tested at a time, the more savings can be incurred in cost and process time.

Generally, when performing wafer testing, a chuck carrying a wafer is raised to a probe card to which thousands of probes are electrically coupled. To test larger wafers, small, high performance probes are needed. The probes must be able to break through the oxide and debris layers on the surface of the contact pads of the chips on the wafer in order to make a reliable electrical contact to each pad. Additionally, the probes must be able to compensate for the fact that the contact pads may be of different heights (i.e., not all the contact pads on a wafer may reside in the same plane). Furthermore, the chuck and the probe card mechanical mount may not be precisely parallel and flat, introducing further height variations which the probes must accommodate.

Conventionally, cantilever wire probes have been used to test wafers in this regard. However, cantilever wire probes are too long and difficult to accurately

assemble to allow reliable simultaneous contact to all of the chips on a conventional wafer. Additionally, cantilever wire probes have high self and mutual inductance problems which do not make them good candidates for testing of high-speed devices. These problems are exaggerated when they are used to test larger wafers. Cantilever (or bending) probes can also be fabricated at a small physical scale by various microfabrication techniques known in the art. These cantilever springs lack the mechanical energy density (for controlled scrubbing of the oxide layer) and spatial efficiency to be ideally effective for reliable testing of large wafers.

A number of attempts have been made to overcome the deficiencies of cantilever probes, all with varied levels of success. For instance, U.S. Patent No. 5,926,951, assigned to Form Factor, Inc., describes methods of producing spring probes by coating a ductile metal with a spring metal (as seen in Figure 4). These springs are bending mode springs similar to cantilever springs. Moreover, they are elongated and poorly supported in lateral directions at the contactor causing problems with controlled scrubbing of the contact pads. Furthermore, probes that require a long spring length such as these have relatively poor electrical performance.

U.S. Patent No. 6,426,638, assigned to Decision Track, describes a torsion spring design, see Figure 1, which is more mechanically efficient than other spring designs, and more effective than cantilever designs. U.S. Patent No. 6,771,084, also assigned to Decision Track, describes the fundamental principle of a single footed torsion spring probe contactor, see Figures 2A and 2B. However these designs too, have their limitations. The particular incarnations considered and contemplated by these patents do not address or solve many of the practical requirements for a spring probe contactor such as: range of motion, optical characteristics required for vision

recognition, practical production means, requirements for high lateral stability of the contact tip in response to scrubbing forces to name a few.

Improvements in the design of probe contactors have come with advances in photolithography and associated micromachining techniques. U.S. Patent No. 5,190,637 to Wisconsin Alumni Research Foundation describes the basis of multi-layer build up fabrication through lithographic electro-forming techniques of three-dimensional metal structures including springs and spring contactors. The present applicants have created a micro-formed torsion bar probe contactor which overcomes many of the deficiencies of the prior art and is a subject of the instant application.

Another aspect of the present application is the formation of the tip at the end of the probe. Older pin based contactors, such as cantilever needle probes or vertically buckling beam probes, are typically built from wire with a sharpened or shaped tip. This type of geometry provides for adequate electrical contact only if substantial contact force is applied. High contact force is deleterious to the semiconductor devices under test which often include active devices under the I/O pads. Furthermore, pin based contactors cannot be built at the fine pitches and high pin counts required for modern large wafer test. For these and other reasons, microfabricated probe contactors are an attractive alternative to pin based probe cards.

Microfabricated probe contact tips for use on contactor probes have been proposed in a variety of configurations and are plentiful in the art. In most of these configurations, provision is made for the creation of a tip with a well defined and controlled surface shape, size, material, and texture. Each of these elements is important for achieving the required consistent electrical contact to common IC pad metals such as Al, AlSiCu, Cu, Cu alloys, Au, or solder. Each of these parameters

has a bearing on the contact performance but control over the geometry is among the most significant and is a function of the fabrication technology employed.

Another factor that is often overlooked is the optical characteristic of the tip and adjacent structures. Typically, probe cards are used in conjunction with wafer probers equipped with machine vision systems for automatic identification of probe tip locations and alignment of those to the I/O pads on the wafer, such as that described by U.S. Patent No. 5,321,352, assigned to Tokyo Electron Labs. Basically, a machine vision system includes a camera that is positionable and looks at the tips of the probe needles. The camera has some magnification appropriate for viewing the geometry of the tip. It also includes a light source such as an LED ring light or a co-axial light. The image from the camera is processed by computer so as to determine the location of the tip relative to the camera's image area. This location information is used by the prober's computer control algorithm to position the device-under-test (DUT) bond pads accurately under the probe tips. Thus the probe tip must be designed with the vision systems requirements in mind. In particular, vision systems require a good optical contrast between the tip and adjacent structures, particularly in the case of microfabricated contactors with small physical dimensions between adjacent surfaces. Typical microfabricated spring contactors have smooth planar surfaces in close proximity to the contact tip surface, creating difficulty with regard to the vision recognition systems due to reflections from surfaces other than the tip, as seen in Figure 5A. Thus, these vision systems often mistake unrelated structures for the tip causing vision rejections or errors in the captured tip position.

Various attempts to overcome this problem have been suggested, but each have had their own problems. For instance, U.S. Patent No. 6,255,126, assigned to Form Factor, Inc. and shown in Figures 3A and 3B, discloses a pyramid shaped

contactor tip for use with a cantilever probe structure. The pyramid is formed by replicating an anisotropically etched cavity in silicon and bonding the replicated tip to a spring structure. While this technique may produce a tip with a good mechanical strength due to its wide base, and the sides of the pyramid reflect light off-axis and appear dark under the normal illumination used for machine vision recognition, this design has at least two significant drawbacks. The fabrication sequence is driven by a mold replication technique and requires a separate bonding step in order to assemble the tip to the spring. This extra bonding step adds significant complexity, yield loss, and cost to the manufacturing process. Furthermore, the pyramid shape produces a contact geometry that is limited to a square or rectangular contact surface which grows in size as it is abraded or re-surfaced as is often done in practical application as a result of abrasive cleaning. Any change in surface shape or size results in a change in contact area and hence electrical contact characteristics as well as scrub mark.

Another way of solving machine vision problems is to create the tip significantly tall (approximately 50  $\mu\text{m}$  tall). In this embodiment, the next underlying planar surface (the post) would be far enough away from the focal plane of the vision microscope so that the post surface would be out of focus and only the tip would be in focus. However, this is not a practical solution for tips that are produced by lithographic imaging and electroforming. Such processes have practical limits in aspect ratio (height to width ratio). Furthermore, even if the aspect ratios of a taller tip were practical (typical tips are about the same height as or slightly higher than their smallest dimension which is on the order of 5  $\mu\text{m}$  to 20  $\mu\text{m}$ ), a taller tip would be prone to breakage from the lateral scrubbing forces present in use.

Another proposed alternative is to remove part of the post structure, creating a sloped surface around the tip, see Figure 5B, that cannot reflect illumination back to

the vision system. However, a problem with this design is that it is very difficult to align a tip on the flat top of the now tapered post. Any slight misalignment provides a planar reflective surface near the tip base and causes a bright “crescent” to appear around the tip. The crescent effect interferes with proper tip-position recognition causing vision “rejects” or errors in the captured visual centroid.

Thus a new design is needed for creating a tip and post structure that will resolve the issues of vision errors when a tip is lithographically formed on a probe structure.

SUMMARY OF THE INVENTION

Improvements upon the lithography techniques described in U.S. Patent No. 5,190,637 are the subject of U.S. Patent Application Serial Nos. 11/019912 and 11/102982, both commonly owned by the present applicant and hereby also incorporated by reference. Those two applications describe the use of general photolithographic pattern-plating techniques combined with the use of islands of sacrificial metals to further create microstructures such as probe contactors. Using the above techniques, the present applicants have created a micro-formed torsion bar probe contactor which overcomes many of the deficiencies of the prior art and that is a subject of the instant application.

The present invention is directed to a probe incorporating a torsion bar as a spring element and a tip and post structure that resolves current problems with automatic vision mechanisms. The torsion bar probe is formed on a substrate which will ultimately hold hundreds or thousands of probe elements. The probe is connected to the substrate by a foot. Attached to one end of the foot is a trace that electrically connects the foot to a via in the substrate, and at the other end of the foot, a torsion bar is attached. At the other end of the torsion bar, a spacer is attached, the spacer being taller than the torsion bar. Atop the spacer, an arm is attached. The arm is more rigid than the torsion bar, meaning that it does not significantly bend to store energy during use. Atop the arm, opposite the spacer, a post (or posts) are attached, and atop the post(s) is a tip, the structure of which will be described further below. A stop is built atop the substrate at a place near and below where the spacer and torsion bar are joined. There is a space or a gap between the torsion bar and the stop when the probe is in a non-actuated state (i.e., not pressed against a contact pad of a semiconductor device).



In operation, the tip is contacted by an I/O contact pad on a wafer and forced down (in the spatial orientation of the majority of the drawings) towards the substrate. As the tip is pushed down, the arm, which is designed to be mostly rigid, tilts causing the torsion bar to twist. The torsion bar is firmly affixed to the substrate at the foot end, and is supported both vertically and laterally, but free to rotate, at the stop end. Rotation at the stop end involves a slight motion of the torsion bar (through the gap distance of a few microns) until contact is made to the stop, after which point the torsion bar pivots against the stop. The overall geometry of the probe (including spacer height, arm length, post height, etc.) dictates the motion in space of the tip as it travels downward. The motion is largely in the form of an arc, providing a forward component (in a direction roughly orthogonal to the axis of the torsion bar) as the tip moves downward. The forward motion of the tip provides the “scrub” which is necessary in practice to achieve a good reliable and repeatable contact resistance to the I/O pad.

Utilizing the manufacturing processes described in U.S. Patent Application Serial Nos. 11/019912 and 11/102982, the present invention includes several novel features not present in the prior art. One of the novel features of the present invention is that the arm portion is in a different planar layer than the torsion bar and may be separated from the torsion bar by a spacer. The addition of these two added layers provides for greater design flexibility towards controlling the path of motion of the tip when it is actuated by a largely vertical force when testing a device. The availability of additional layers of the probe in this respect is made possible by the new manufacturing processes described in the above patent applications. In fact, as described, the torsion probe has at least eight planar layers utilized in the construction of the torsion contactor spring and these layers afford design flexibility to optimize

the operational characteristics of the contactor while accommodating the process limitations imposed by commercially viable photolithographic micro-electro-forming techniques. The torsion probe may have more or fewer layers than eight without departing from the spirit of this invention.

The arm of the probe is also made more rigid than the torsion bar so that it does not act as a spring (as in a cantilever beam spring). If the bar was not rigid, its deformation would increase the scrub length beyond that which may be desired. The arm provides a lever which, in consort with the stop, transforms the largely linear arc of the tip to a nearly pure-torsion rotation of the torsion bar. In another embodiment, the arm is composed of two subarms, one extending from the top of the end of the other. This approach allows a greater clearance between the closest part of the spring structure and the wafer under test. Additional clearance helps to avoid damage to the wafer from foreign particles that may become caught between the probe structures and the wafer in the contacted state.

Another novel aspect of the present invention is that a stop is attached to the substrate and incorporates a lateral support to laterally support the torsion bar when it engages the stop. The basic function of the stop is to act as a fulcrum or pivot for the torsion bar. The lateral support provides an increase in lateral stability and more control over the tip's scrub pattern.

Another novel aspect of the present invention is the design of the tip and post structure. To ensure that the machine vision systems can accurately differentiate the tip from the post when both have planar surfaces, the top portion of the post, to which the tip is coupled, is treated in such a way that it diffuses or absorbs incident light. This can be accomplished several ways, such as through rough plating (such as with

high current plating with or without the addition of grain refiners) or metallographic decorative etching.

A further refinement is to provide a rough plated skirt that covers not only the top surface of the support post, but also wraps around the base of the tip. This construction not only creates a high contrast between the tip surface and the post but also provides for mechanical support of the tip in the form of a thickening or gusset around its base. The gusset further protects the tip from mechanical failure at its base caused by lateral forces during use, which is particularly useful if the tip has a high aspect ratio (height to width or diameter). This skirt may also be plated in a pattern that slightly overhangs the post structure so that slight misalignments (e.g., due to lithography errors) do not result in the exposure of the smooth reflective surface in the shape of a crescent or edge at one side of the perimeter of the post.

BRIEF DESCRIPTION OF THE DRAWINGS

FIGURES 1 – 5B are examples of embodiments of the prior art.

FIGURE 6A illustrates a side view of an embodiment of the present invention.

FIGURE 6B illustrates a side view of another embodiment of the present invention.

FIGURE 6C illustrates a side view of another an embodiment of the present invention.

FIGURE 7A illustrates a perspective view of the embodiment of the invention shown in FIGURE 6B.

FIGURE 7B illustrates a perspective view of the embodiment of the invention shown in FIGURE 6C.

FIGURE 8 shows a top down view of the embodiment of FIGURE 6A.

FIGURE 9 shows a view of the embodiment of the invention in FIGURE 6A, as seen from the front of the stop element.

FIGURE 10 illustrates an embodiment of the stop element of the present invention.

FIGURE 11 illustrates another embodiment of the stop element of the present invention.

FIGURE 12 illustrates another embodiment of the stop element of the present invention.

FIGURE 13A shows a side view of the embodiment of FIGURE 6A in an actuated state.

FIGURE 13B shows a side view of the embodiment of FIGURE 6C in an actuated state.

FIGURES 14A-14E illustrates the twisting of the torsion bar as an embodiment of the invention is placed in an actuated stated.

FIGURE 15 illustrates an embodiment of the tip design of the present invention.

FIGURE 16 illustrates another embodiment of the tip design of the present invention.

FIGURE 17A illustrates a perspective view of another embodiment of the tip design of the present invention.

FIGURE 17B illustrates a cut-away view of the Figure of 17 A.

FIGURE 18 illustrates a close-up view of an embodiment of the tip design of the present invention.

DETAILED DESCRIPTION

FIGURE 6A shows a probe for testing an electronic device in accordance with an embodiment of the present invention. This embodiment of the probe incorporates a substrate 600, a trace layer 610, a foot element 620, a torsion bar 630, a spacer element 640, an arm 650, a post 660, a secondary post 670, a tip 680, and a stop element 690. Plated on a substrate 600 is a trace layer 610 providing an electrically conductive path from the foot 620 to a via 900 (see Figure 9) in the substrate 600. This trace layer 610 may be electroplated gold having a nominal height (also termed thickness) of 16  $\mu\text{m}$ . The foot 620 provides the mechanical anchor for the probe. The foot 620 has both a proximal end (the end closest to the via 900) and a distal end (the end furthest from the via 900). The foot 620 is connected to a torsion bar 630 at its distal end. The torsion bar 630 is the element which provides the probe with its spring like (or compliant) qualities because when it is in an actuated state (i.e., when the probe is contacting an I/O pad of a semiconductor device), the torsion bar 630 will twist as is shown in Figures 14A- 14E. In one embodiment, the torsion bar 630 is non-axially aligned with the foot 620. In one embodiment, the torsion bar 630 is at an angle of about 10 to about 90 degrees relative to the foot 620, but preferably it is at about a 20 degree angle. This non-axial placement provides an increased strength in the attachment between the foot 620 and the substrate 600, by increasing the moment arm of the attachment, and thereby lessening the peeling forces imparted by the torsion bar 630 on the foot/substrate interface during operation. The torsion bar 630 is raised off of the substrate 600 so that it is not touching it. At its distal end, the torsion bar 630 may have a lateral support element 920 (see Figures 9 and 10) which will be used in conjunction with the stop 690 to prevent lateral displacement of the torsion bar 630 during actuation.

At the distal end (again, the side that is furthest from the via 900) the torsion bar 630 is coupled to a spacer element 640. The spacer element raises the arm element 650 off from the plane of the torsion bar 630. The spacer element 640 provides design flexibility towards controlling the path of the motion of the tip 680. It also provides the clearance required between the arm 650 and the substrate 600 to accommodate a full range of compliance. On top of the spacer 640, is the arm element 650. The arm element 650 is plated generally non-axial to the torsion bar 630. In one embodiment, the arm 650 is at an angle of about 20 to about 160 degrees relative to the torsion bar 630, and preferably the angle is about 120 degrees. The arm 650 is designed to be rigid so that it does not act as a spring. If the arm 650 were especially flexible, its deformation would contribute to increasing the scrub beyond the desired limit. In this regard, the arm 650 may be made of a higher modulus metal (for example, W) than the torsion bar 630 (formed from, for example, NiMn), or it may be made shorter, thicker (increasing the height) or wider (or any combination) than the torsion bar 630 as in the preferred embodiment. In this regard, the length, thickness, and width can be expressed in the three axes of three-dimensional Cartesian coordinates, conventionally denoted the x, y, and z axis. The x-axis represents the length, the y-axis represents the width, and the z-axis represents the thickness.

The fact that the arm 650 is on a different plane than the torsion bar 630 is a novel feature of the present invention. This feature is made possible by the use of the photolithography process described in U.S. Application Nos. 11/019912 and 11/102982, which are incorporated herein by reference.

Atop the distal end of the arm 650, a first post 660 is plated. The first post element 660 also provides design flexibility in controlling the path of the motion of the tip 680 during actuation. The first post 660 may have a tip 680 plated on top of it,

or there may be a second (or more) post element(s) 670, optionally having a smaller surface area than the first post element 660, plated between the first post 660 and the tip 680. The post element (either a first post 660 or combined with the secondary post element 670) extends the tip 680 vertically away from the arm 650 allowing the full target deflection of the tip. The secondary post 670 may be added to the first post 660 to allow proper geometries for tip scrub while maintaining manufacturability. The first post 660 may be plated large enough to allow lithography and plating with a roughly (or slightly larger) 1:1 aspect ratio (width to height). The secondary post 670 is ideally smaller in order to more adequately accommodate a proper scrub. A smaller secondary post 670 also accommodates lithographic alignment errors between the two post layers.

The tip 680 does not need to be concentric with whichever post (660 or 670) it is plated on. It may be advantageous to plate the tip 680 offset from the center of the post (660 or 670) upon which it is plated in order to eliminate any interference the post (660 or 670) may have with the device under test due to the deflection angle. The tip 680 may be circular, rectangular, blade-shaped, oval, teardrop shaped, or any other shape that can be formed lithographically.

Underneath the arm 630 is a stop element 690. The stop element 690 is plated on the substrate 600 and there is a gap 910 (see Figure 9 and 10) between the arm 630 and the stop 690. The gap 910 may be formed by plating approximately 1  $\mu\text{m}$  to approximately 20  $\mu\text{m}$  of sacrificial copper between the stop 690 and the torsion bar 630 during manufacture, and preferably about 6  $\mu\text{m}$  of sacrificial copper is plated. The sacrificial metal will then be removed in the final stages of production of the probe. The stop 690 is designed to provide vertical and lateral support to the torsion bar 630 when the probe is in an actuated state. The basic function of the stop 690 is to



act as a fulcrum or pivot for the torsion bar 630. In one implementation, the stop 690 is partially “buried” under the torsion bar 630 in a shallow pocket formed by the lateral support element 920 of the torsion bar 630 (see figures 9 and 10). In another embodiment, the stop 690 is completely placed under the distal end of the torsion bar 630 (see Figure 11). In the latter embodiment, the stop 690 may also incorporate a lateral support element 1100 and the torsion bar 630 may incorporate two lateral support elements 920 on either side of the stop lateral support element 1100. This embodiment laterally supports the torsion bar 630 in both the positive and negative x directions, providing better lateral stability and scrub mark position accuracy. Figure 12 also shows another embodiment of the stop element 690. In this embodiment, the torsion bar 630 has one lateral support element 920 and the stop 690 has two lateral support elements 1100 on either side. Other stop configurations providing a pivot while constraining lateral motion may be implemented without departing from the spirit of this invention.

Figure 6B depicts an alternative embodiment of the present invention. In this alternative embodiment, a second trace layer 695 (which may be connected to trace layer 610) is also plated underneath the stop 690. The purpose of this second trace layer 695 is so that the stop layer 690 can be plated in the same plane as the foot 620. This feature also reduces the thickness of the spacer element 640

Figure 6C depicts an alternative embodiment of the present invention. This alternative embodiment is substantially the same as Figure 6B but shows a probe element with a first arm 650 attached to the torsion bar 630 and a second arm 655 that sits at the distal end of the first arm 650. Because of the dual arm structure, a spacer 640 is not necessary. The dual-arm feature allows for greater clearance between the closest part of the probe structure and the wafer under test. Additional clearance can

help avoid damage to the wafer surface from foreign particles caught between the probe structure and the wafer surface in the actuated state. This is graphically shown in Figures 13A and 13B. Figure 13A shows an embodiment like that in Figure 6A or 6B. In one embodiment, the proximal end of the arm 650 (the end furthest from the tip 680) may be less than 20  $\mu\text{m}$  from the wafer under test 1300. In Figure 13B, the lowest part of the second arm 655 may be roughly 45  $\mu\text{m}$  from the wafer under test 1300 and the lowest part of the arm 650 may be roughly 56  $\mu\text{m}$  from the wafer under test 1300. In both Figures 13A and 13B, it is assumed that the probe structure traveled 100  $\mu\text{m}$  which is the distance between the substrate 600 and the lowest part of the arm (or first arm) 650.

One could increase the height of the posts 660, 670 in order to create greater clearance between the wafer surface and the probe structure, but this is undesirable because it increases scrub length and adds process complexity and cost. While the embodiment shown in Figure 6C shows a dual arm structure, a probe may be constructed with many more arms without parting from the spirit of the present invention. It is also possible to replace the post with a short arm (the difference being that a post has roughly equal length and width or may be round while an arm is substantially longer than it is wide).

Figure 7A depicts the embodiment of Figure 6A from an angle which shows the non-axial alignment of the torsion bar 630 to the foot 620, and the non-axial alignment of the arm 650 to the torsion bar 630.

Figure 7B depicts the embodiment of Figure 6C from an angle which shows the non-axial alignment of the torsion bar 630 to the foot 620, and the non-axial alignment of the arms 650 and 655 to the torsion bar 630.

Figure 8 shows a top down view of the embodiment of the present invention shown in Figure 6A.

Figure 9 is a perspective view of Figure of 6A. It is the view of Figure 6A one would see if he was looking straight-on at the stop 690 with the torsion bar 630 being behind the stop 690.

In an embodiment of the present invention shown in Figure 6A the trace layer 610 may be a layer of Ni or NiMn plated 25 um high which in turn may also be plated on a conductive base layer that may be 2000 A Cr under 5000 A of Au under 15 um of electroplated Au. The stop 690 maybe a layer of Ni or NiMn plated to a height of 28 um, and the foot 620 may be plated in two sections: one plated at the same time as the stop 690, the other plated at the same time as the torsion bar 630. Overall, the foot 620 may be a layer of Ni or NiMn (or a combination of both) plated to a height of 67 um. The torsion bar 630 may consist of NiMn that is 39 um high. It should be understood that this is the thickness (in height) of the torsion bar 630, not the height of the torsion bar from the plane of the substrate 600. The torsion bar 630 may also be 40 um in thickness and 804 um in length. NiMn is a useful alloy for the creation of the torsion bar 630 because of its spring like qualities. The arm 650 may be NiMn or Ni plated to a height of 60 um, a width of 55 um and a length of 473 um. The first post 660 may be Ni or NiMn plated to a height of 68 um and the second post 670 maybe be Ni or NiMn plated to 28 um. The tip 680 may be PdCo or Rh plated to a thickness of 11 um or it may be a combination of Ni or NiMn and RdCo or Rh totaling 11 um in thickness.

In the embodiment of the Figure of 6A, there may be a distance of 100 um from the top plane of the arm 650 and the top plane of the tip 680. There may also be a distance of 110 um between the top plane of the substrate 600 and the bottom plane

of the arm 650. The total distance from the top plane of the tip 680 and the top plane of the substrate 600 may be 270  $\mu\text{m}$ .

In the embodiment of Figure 6C, the distance between the top plane of the first arm 650 and the top plane of the tip 680 may be 148  $\mu\text{m}$  and the distance between the top plane of the second arm 655 and the top plane of the tip 680 may be 93  $\mu\text{m}$ . The distance between the top plane of the substrate 600 and the bottom plane of the second arm 655 may be 125  $\mu\text{m}$ .

While the forgoing dimensions give approximate dimensions for exemplary embodiments of the present invention, the actual dimensions may be varied by as much as ten times without significantly altering the design principles utilized. While Ni is utilized to make a majority of the probe element in the above examples, many other metals and metal alloys such as NiMn, Tungsten Alloys, and Cobalt alloys may also be used. In general, it is desirable to use metals that can be electroformed and that provide good mechanical strength, toughness and thermal stability.

The substrate 600 may be any type of substrate, including semiconductor materials such as silicon, germanium and gallium arsenide, ceramics such as alumina, aluminum nitride, glass bonded ceramics, low temperature cofired ceramics (LTCC) and high temperature cofired ceramics (HTCC), dielectric coated metals or glasses. The substrate 100 is preferably a Low Temperature Co-fired Ceramic (LTCC) substrate with built in vias 900 such that electricity may be conducted from one face 600a of the substrate 600 to the other face 600b of the substrate 600 by way of the vias 900. In an embodiment of the present invention, the vias 900 are made from gold, but any other conductor such as copper, tungsten or platinum may be used. The ceramic may also contain electrical redistribution conductors, making it an electrical wiring board or "space transformer" as is commonly known in the art.

Another novel feature of the present invention is the design of the tip and post structures on the probe. The quality and reliability of the electrical contact to a semiconductor I/O pad is a function of the tip material, tip size, tip geometry, scrub motion, and contact force. Each of these parameters has a bearing on the contact performance, but tip geometry is among the most significant and is a function of the fabrication technology employed. Older contactors, such as cantilever needle probes or vertical buckling beam probes were typically built from wire with a sharpened or shaped tip. However, this type of tip geometry is difficult to control at the micron scale and requires high contact force which is deleterious to the semiconductor devices under test. Furthermore, pin based contactors cannot be built at the fine pitches and high pin counts required for modern wafer test. For these and other reasons, microfabricated probe contactors are an attractive alternative. New microfabricated spring contactors often have smooth planar surfaces in close proximity to the contact surface which creates difficulty for automatic vision systems to easily identify the tip due to reflections from surfaces other than the tip. The new post and tip designs of the present invention overcome this common problem.

Figure 15 shows one embodiment of the tip and post design of the present invention. In Figure 15, the bottom (in the view shown) of the post 670 has a roughened surface 1500. The surface is roughened prior to lithographically pattern-plating the tip 680 on the post 670, and so the tip 680 is plated directly on the roughened surface 1500. The roughened surface 1500 can be formed by plating metals and alloys such as Ni, Ni alloys such as NiMn, NiCo, NiW, or NiFe, W alloys such as CoW, Cr or similar metals at a high current, or by the addition of grain refiners or other additives such as Mn salt in a Ni Sufamate bath, or in any other manner known in the art of electroplating and electroforming to create a roughened

surface. As shown in Figure 18 (not drawn to scale), the roughened surface 1500 may have peaks 1510 and valleys 1520 and a peak 1510 may rise up approximately .1  $\mu\text{m}$  to approximately 5  $\mu\text{m}$  from a valley 1520, and preferably the height is approximately 1  $\mu\text{m}$  from peak 1510 to valley 1520. The arrows in Figure 15 denote light (the solid lines indicate intense light, the dashed lines indicate diffused, diffracted, absorbed, or in some other way, less intense light). Thus, Figure 15 shows that the light reflected back from the roughened surface 1500 is diffused and scattered. This helps the automatic vision systems to resolve the tip 680 more clearly by providing greatly improved contrast between the tip and the post surface(s).

A further refinement to this idea is depicted in Figure 16. In Figure 16, a rough plated skirt 1720 is plated on the bottom portion of the post 670 and also around the base of the tip 680. This construction creates a high contrast between the surface of the tip 680 and the post 670 and also provides for mechanical support of the tip 680 in the form of a thickening or gusset around the base of the tip 680. The gusset further protects the tip 680 from mechanical failure at its base caused by lateral forces during use, particularly if the tip 680 has a high aspect ratio (height to width or diameter).

Figures 17A and 17B depict another embodiment of the tip and post design of the present invention. In Figures 17A and B a roughened metal is plated in a cap 1710, 1700 over the posts 670, 660 so that the metal overhangs the post structures. This fabrication method insures that slight misalignments (due to lithography errors) do not result in the exposure of the smooth reflective surfaces of the posts 660, 670 which could cause a crescent or edge at one side of the perimeter of the posts 660, 670.

While the description above refers to particular embodiments of the present invention, it should be readily apparent to people of ordinary skill in the art that a number of modifications may be made without departing from the spirit thereof. The accompanying claims are intended to cover such modifications as would fall within the true spirit and scope of the invention. The presently disclosed embodiments are, therefore, to be considered in all respects as illustrative and not restrictive, the scope of the invention being indicated by the appended claims rather than the foregoing description. All changes that come within the meaning of and range of equivalency of the claims are intended to be embraced therein.

CLAIMS

What is claimed is:

1. A microfabricated structure, comprising:  
a post having a rough top surface with a surface area and the top surface having a property of diffusing, diffracting, or absorbing incident light; and  
a tip, lithographically pattern-plated on the rough top surface of the post, having a smooth reflective surface suitable for machine recognition systems, and having a contact surface area that is less than the surface area of the top surface of the post.
2. The microfabricated structure of claim 1, wherein the top surface includes metal plated at a high current.
3. The microfabricated structure of claim 1, wherein the top surface is etched to a rough finish.
4. The microfabricated tip and post structure of claim 1, wherein the top surface is metal plated with at least one additive to provide roughness.
5. The microfabricated structure of claim 2, wherein the metal is one of Ni, NiCo, NiW, NiFe, CoW, Cr, or NiMn.
6. The microfabricated structure of claim 4, wherein the at least one additive is Mn salt in a Ni Sufamate bath.
7. The microfabricated structure of claim 5, wherein the at least one additive is a grain refiner.
8. The microfabricated structure of claim 1, wherein the tip is non-centered on the post.
9. The microfabricated structure of claim 1, wherein the post is approximately 28 um in height.



10. The microfabricated structure of claim 1, wherein the tip is composed of either PdCo or Rh.
11. The microfabricated structure of claim 1, wherein the tip is approximately 11  $\mu\text{m}$  in height.
12. The method of creating a microfabricated structure, comprising:
  - lithographically pattern-plating a post on a surface of a microfabricated probe structure;
  - rough plating a top surface of the post, said top surface having an area, and said top surface having a property of at least one of diffusing, diffracting, or absorbing light;
  - lithographically pattern-plating a tip having a smaller area than the area of the top surface of the post on the top surface of the post, said tip having a reflective surface suitable for machine vision recognition.
13. The method of claim 12, wherein the rough plating includes high current plating of a metal.
14. The method of claim 13, wherein the metal is one of Ni, NiMn, NiCo, NiW, NiFe, CoW, or Cr.
15. The method of claim 12, wherein the rough plating includes incorporating at least one additive into the plating.
16. The method of claim 15, wherein the at least one additive comprises a Mn salt in a Ni Sufamate bath.
17. The method of claim 15, wherein the at least one additive is a grain refiner.
18. The method of claim 12, wherein the reflective surface is smooth.
19. A microfabricated structure, comprising:

a post having a top surface with an area;

a tip having side walls and a top surface, said top surface having a smooth reflective surface appropriate for machine vision recognition of tip position and size, said tip being plated on the top surface of the post, and having an area less than the area of the top surface of the post such that once plated on the top surface, the top surface has an exposed portion and an unexposed portion; and

a skirt plated over the exposed portion of the top surface of the post and over at least a portion of the side walls of the tip, said skirt having a property of at least one of diffusing, diffracting or absorbing light.

20. The microfabricated structure of claim 19, wherein the skirt provides mechanical support to the tip.

21. The microfabricated structure of claim 19, wherein the skirt overhangs the top surface of the post.

22. The microfabricated structure of claim 19, wherein the skirt includes metal plated at high current.

23. The microfabricated structure of claim 22, wherein the metal is one of Ni, NiMn, NiCo, NiW, NiFe, CoW, or Cr.

24. The microfabricated structure of claim 19, wherein the skirt includes at least one additive.

25. The microfabricated structure of claim 24, wherein the additive includes a Mn salt in a bath of Ni Sufamate.

26. A method of forming a microfabricated structure, comprising:  
lithographically pattern-plating a post on a surface of a microfabricated probe structure;

lithographically pattern-plating a tip having a smaller area than the area of the top surface of the post on the top surface of the post creating an exposed portion of the top surface of the post and an unexposed portion of the top surface of the post, said tip having a smooth reflective surface appropriate for automatic vision recognition and side walls; and

plating a skirt over the exposed portion of the top surface of the post and at least over a portion of the side walls of the tip, said skirt having a property of one of diffusing light or absorbing light.

27. The method of claim 26, further including plating the skirt so that it overhangs the top surface of the post.

28. The method of claim 26, wherein the plating the skirt includes plating metal at a high current.

29. The method of claim 28, wherein the metal is one of Ni, NiMn, NiCo, NiW, NiFe, CoW, or Cr.

30. The method of claim 26, wherein the plating the skirt includes incorporating at least one additive into the plating.

31. The method of claim 30, wherein the at least one additive comprises a Mn salt in a Ni Sufamate bath.

32. The method of claim 30, wherein the at least one additive is a grain refiner.

33. A microfabricated structure comprising a tip lithographically pattern-plated on a post, wherein the tip has a smooth surface suitable for automatic vision recognition and the post has a surface that has at least one property that aids an automatic vision recognition system in identifying the tip.

34. The microfabricated structure of claim 33 wherein the property is one of diffusing, diffracting, or absorbing light.

35. The microfabricated structure of claim 1, wherein the top surface has at least one peak and at least one valley.

36. The microfabricated structure of claim 35, wherein the at least one peak rises between approximately .1  $\mu\text{m}$  and 5  $\mu\text{m}$  above the at least one valley.

37. The microfabricated structure of claim 36, wherein the at least one peak rises approximately 1  $\mu\text{m}$  above the at least one valley.

38. The microfabricated structure of claim 19, wherein the skirt has at least one peak and at least one valley.

39. The microfabricated structure of claim 38, wherein the at least one peak rises between approximately .1  $\mu\text{m}$  and 5  $\mu\text{m}$  above the at least one valley.

40. The microfabricated structure of claim 39, wherein the at least one peak rises approximately 1  $\mu\text{m}$  above the at least one valley.

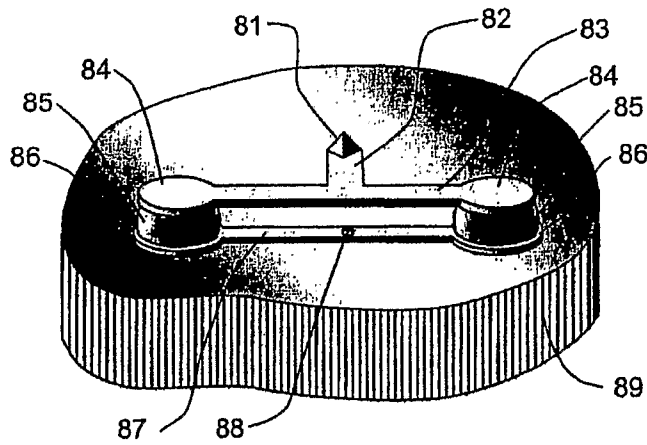


Figure 1  
**Prior Art**

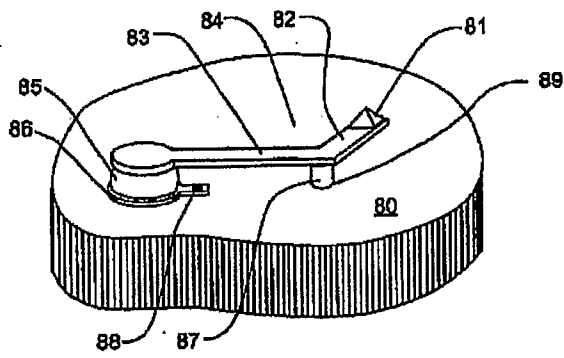


Figure 2A  
**Prior Art**

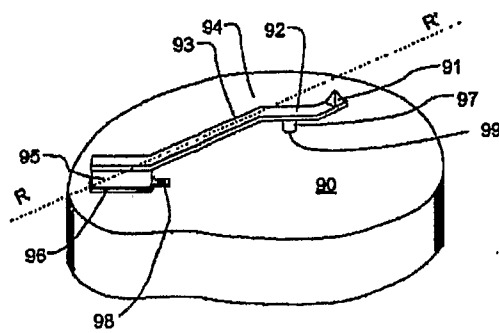


Figure 2B  
**Prior Art**

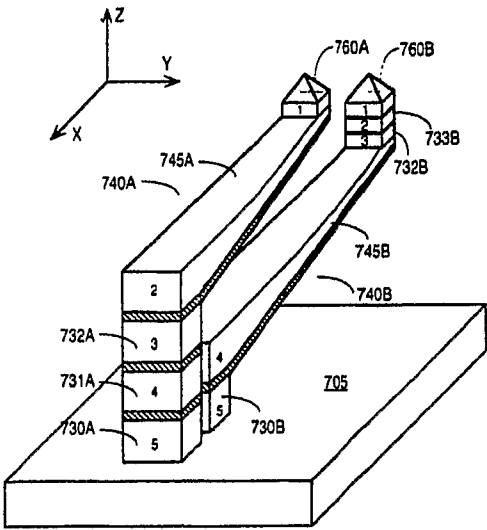


Figure 3A  
Prior Art

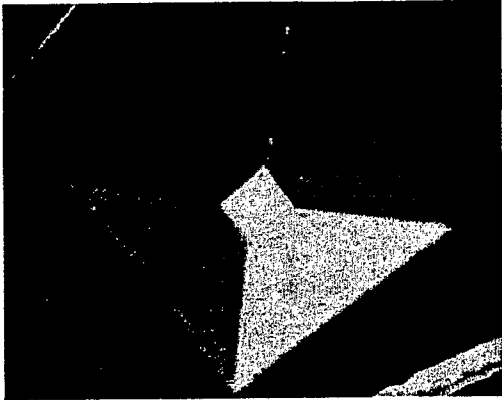


Figure 3B  
Prior Art

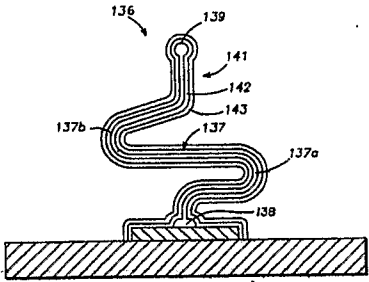


Figure 4  
Prior Art

Figure 5A  
Prior Art

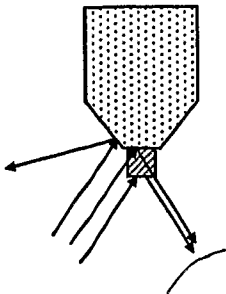
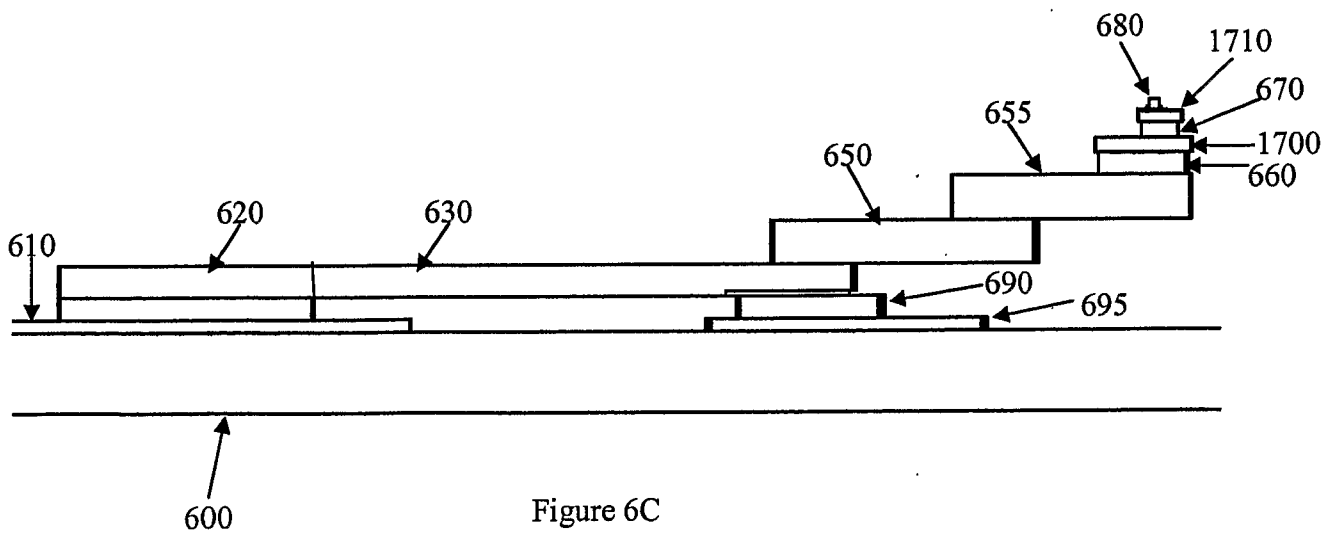
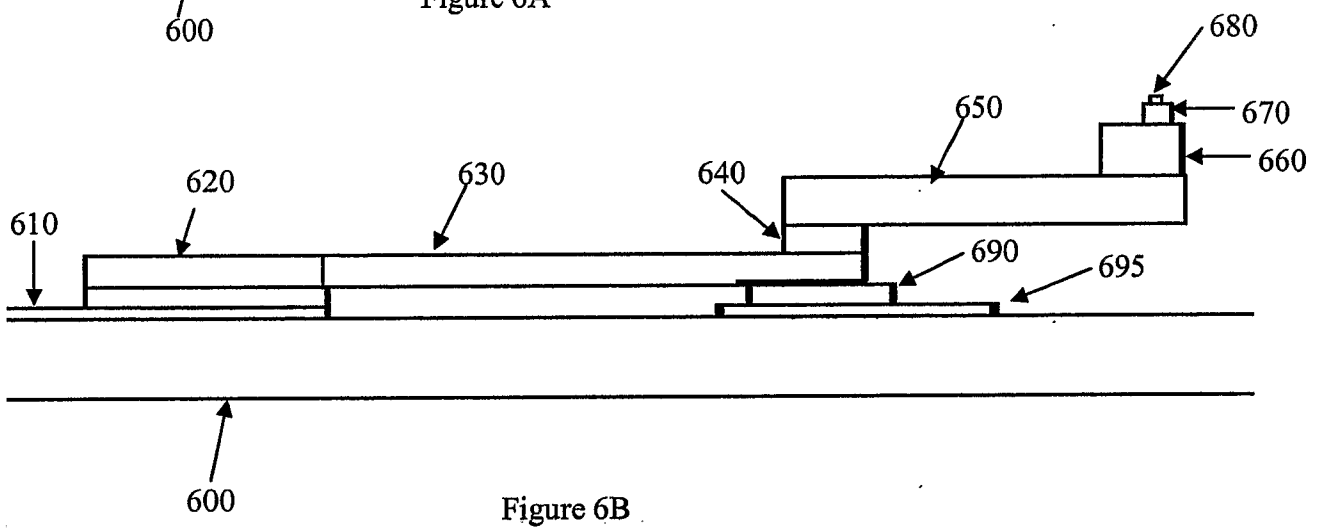
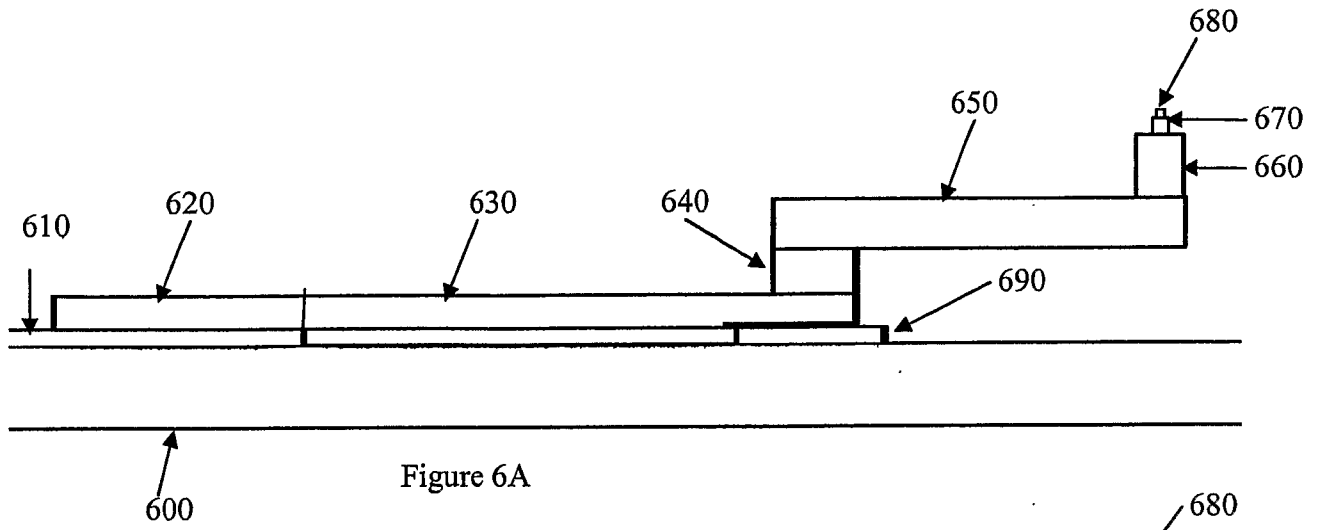


Figure 5B  
Prior Art



4/9

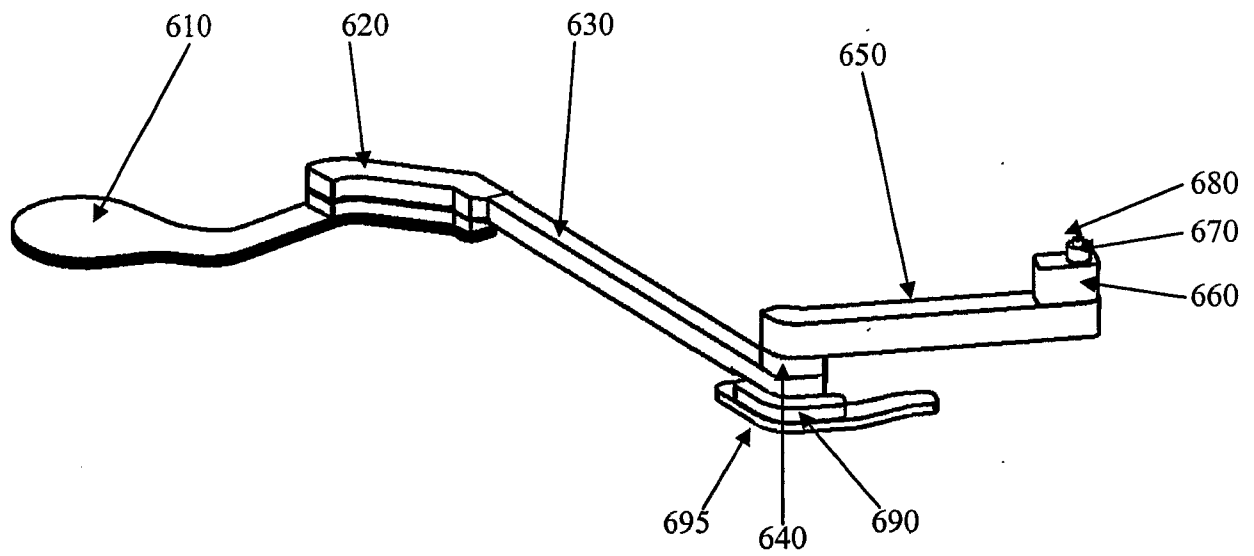


Figure 7A

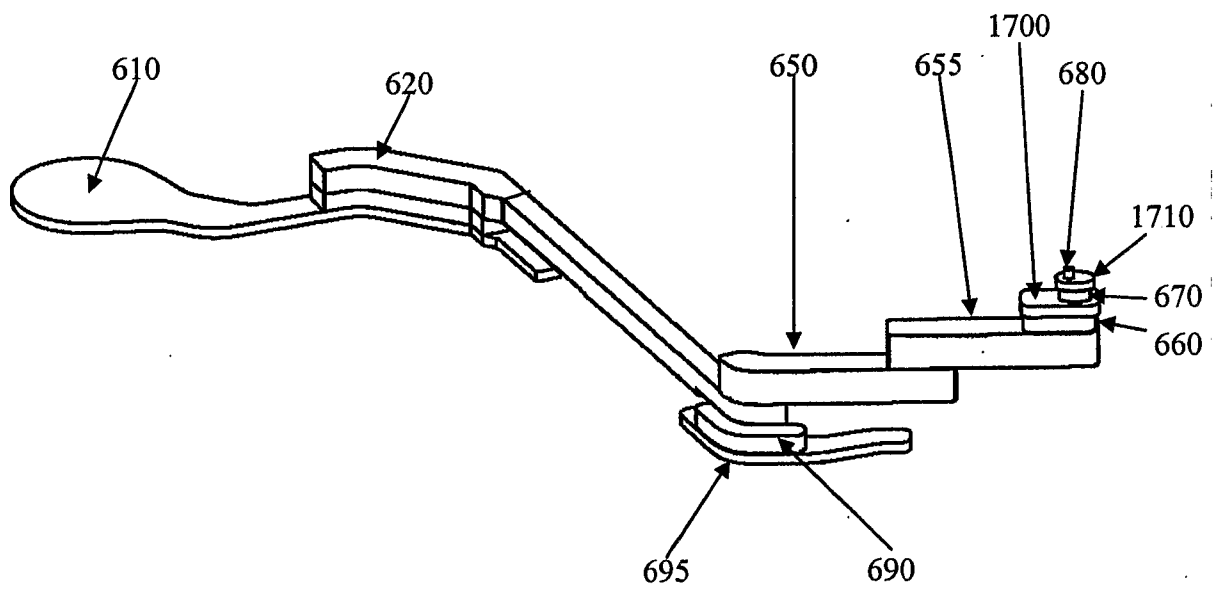
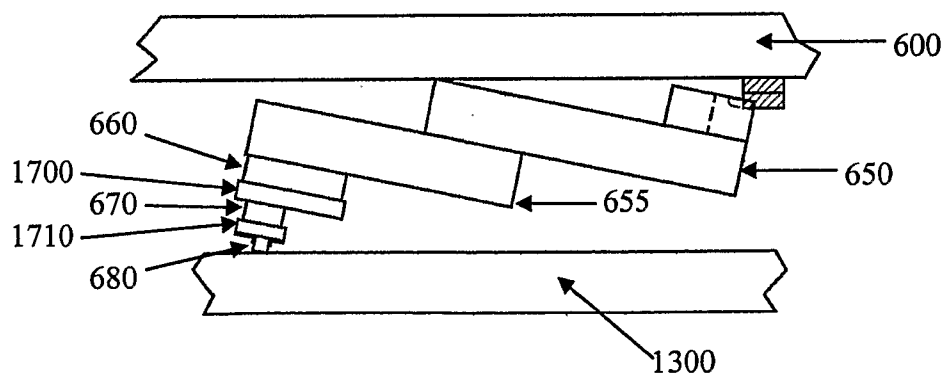
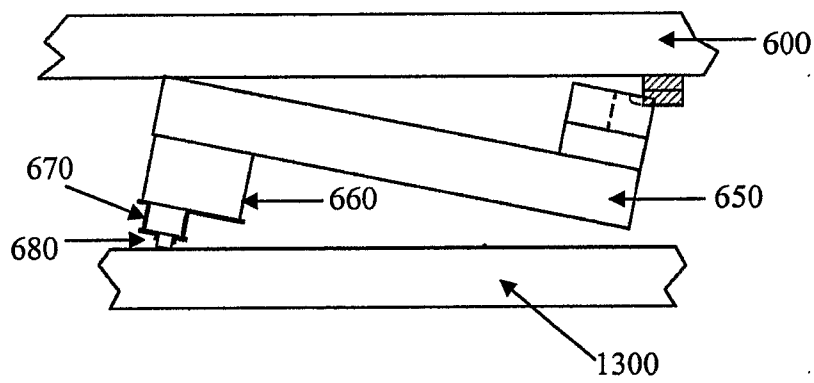
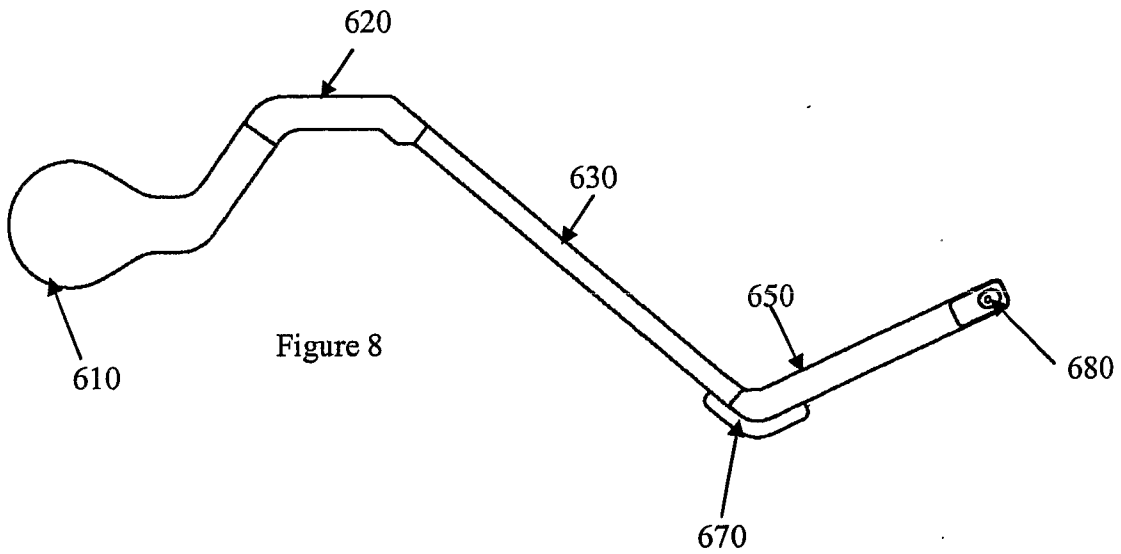


Figure 7B





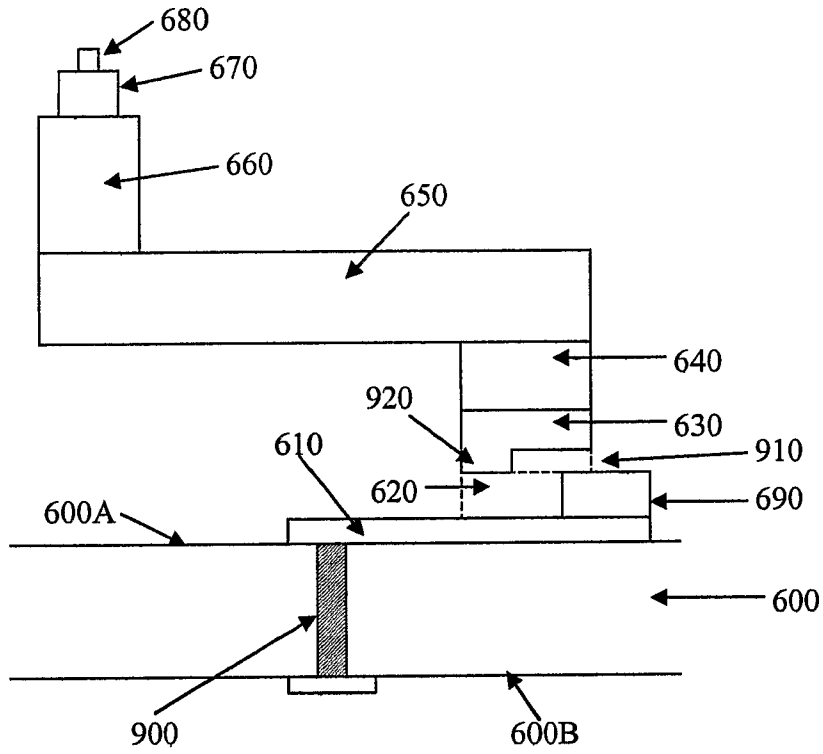


Figure 9

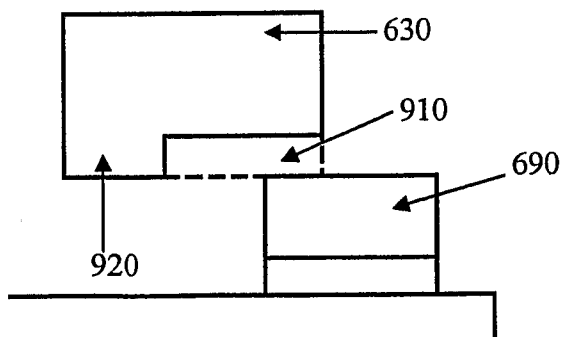


Figure 10

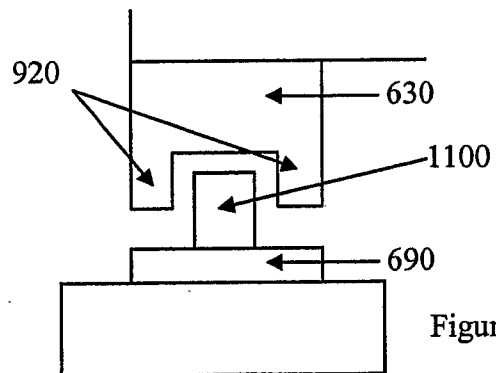


Figure 11

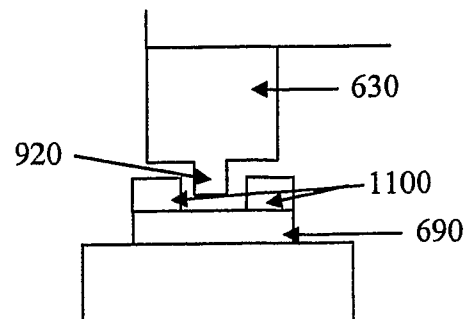


Figure 12

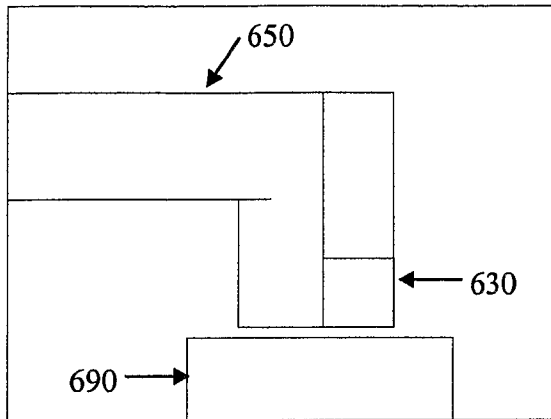


Figure 14A

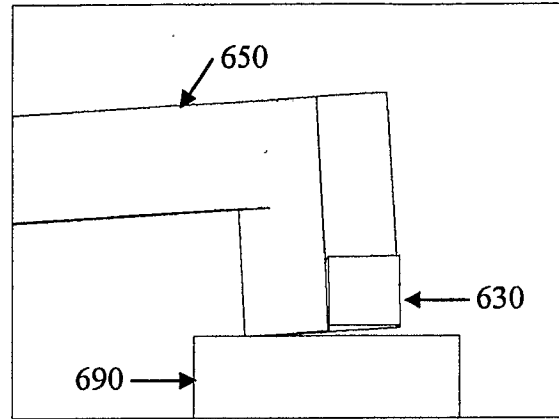


Figure 14B

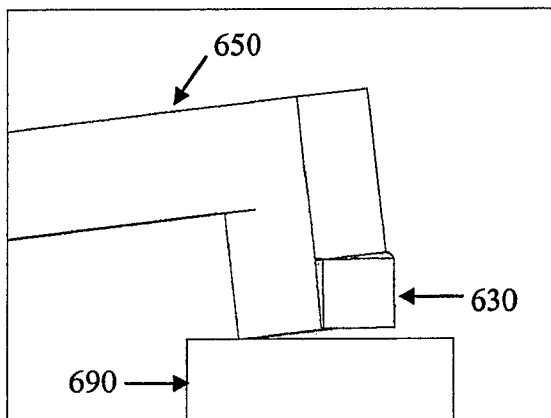


Figure 14C

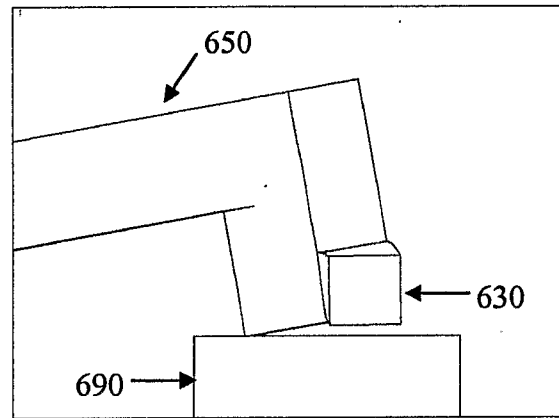


Figure 14D

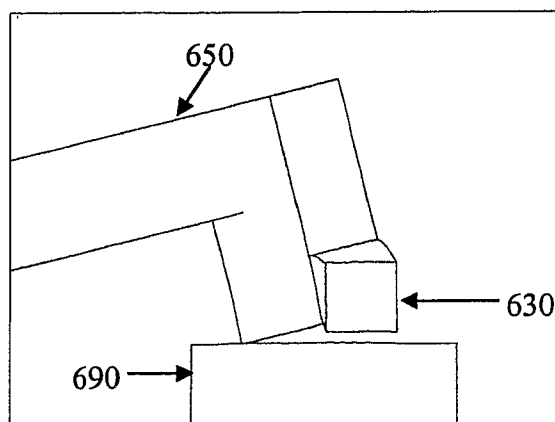


Figure 14E

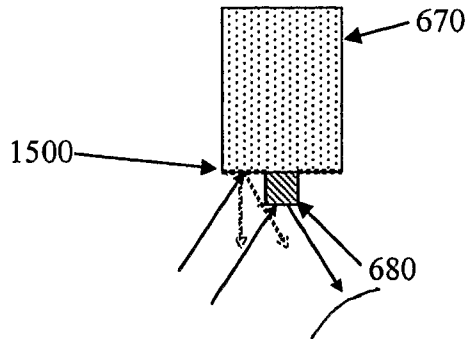


Figure 15

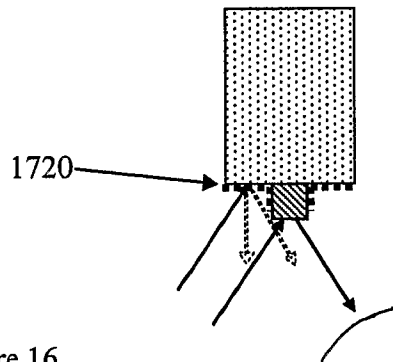


Figure 16

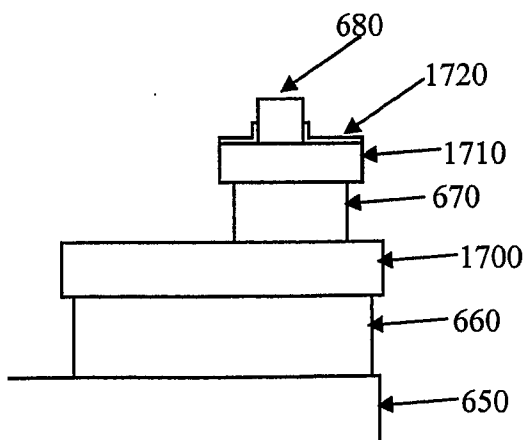


Figure 17B

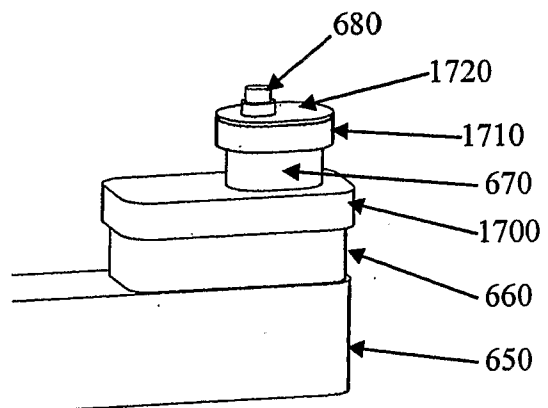
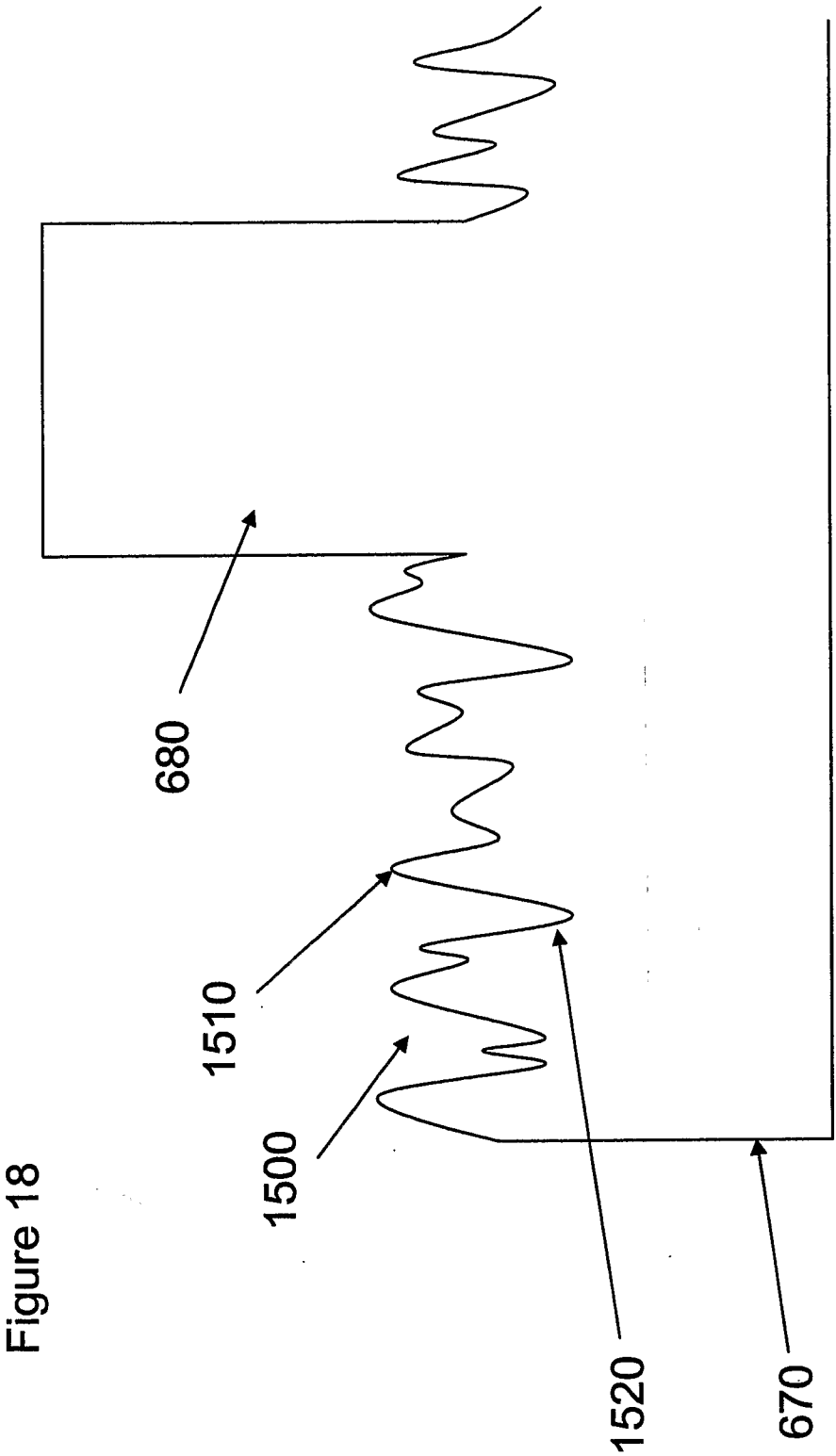


Figure 17A



## INTERNATIONAL SEARCH REPORT

pplication No

/US2005/041665

A. CLASSIFICATION OF SUBJECT MATTER  
G01R1/067

According to International Patent Classification (IPC) or to both national classification and IPC

## B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

G01R H01R

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

EPO-Internal, WPI Data, PAJ

## C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	US 6 578 264 B1 (GLEASON REED ET AL) 17 June 2003 (2003-06-17) figures 20-23,31-38 column 12, line 16 - line 37 column 13, line 65 - column 14, line 19 column 14, line 36 - line 54	1-40
X	US 2004/201392 A1 (KIM TAE MA ET AL) 14 October 2004 (2004-10-14) figures 2-15B abstract paragraphs [0003], [0030], [0031] paragraph [0039] paragraph [0053] - paragraph [0056]	33
A	----- -/--	1, 12, 19, 26

☒ Further documents are listed in the continuation of Box C.☒ See patent family annex.

## \* Special categories of cited documents:

\*A\* document defining the general state of the art which is not considered to be of particular relevance

\*E\* earlier document but published on or after the international filing date

\*L\* document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified)

\*O\* document referring to an oral disclosure, use, exhibition or other means

\*P\* document published prior to the international filing date but later than the priority date claimed

\*T\* later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention

\*X\* document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone

\*Y\* document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art.

\*&amp;\* document member of the same patent family

Date of the actual completion of the international search

21 March 2006

Date of mailing of the international search report

06/04/2006

Name and mailing address of the ISA/

European Patent Office, P.B. 5818 Patentlaan 2  
NL - 2280 HV Rijswijk  
Tel. (+31-70) 340-2040, Tx. 31 651 epo nl,  
Fax: (+31-70) 340-3016

Authorized officer

Höller, H

## INTERNATIONAL SEARCH REPORT

application No  
/US2005/041665

## C(Continuation). DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	US 6 441 315 B1 (ELDRIDGE BENJAMIN N ET AL) 27 August 2002 (2002-08-27) figures 2A-2C, 5F, 5G column 4, line 40 - line 58 column 8, line 48 - line 53 column 10, line 33 - line 55 column 14, line 42 - line 67	33
A		1, 12, 19, 26
A	----- PATENT ABSTRACTS OF JAPAN vol. 2002, no. 06, 4 June 2002 (2002-06-04) -& JP 2002 040052 A (MITSUBISHI MATERIALS CORP), 6 February 2002 (2002-02-06) figures 1, 2, 6-8 abstract paragraphs [0006], [0008], [0009] paragraph [0044] - paragraph [0050] -----	1-40
A	US 2004/070417 A1 (ISA YUKIHIRO) 15 April 2004 (2004-04-15) figures 1, 2, 4 abstract paragraphs [0004], [0011], [0035] paragraph [0047]	1-40
A	----- US 6 208 375 B1 (KAY ROBERT L ET AL) 27 March 2001 (2001-03-27) figures 2, 5 column 8, line 22 - line 40 -----	19-32
A	US 2005/001644 A1 (YOSHIDA HIDEAKI ET AL) 6 January 2005 (2005-01-06) figures 35-39 paragraphs [0047], [0258] -----	33

# INTERNATIONAL SEARCH REPORT

Information on patent family members

ational application No

/US2005/041665

Patent document cited in search report		Publication date		Patent family member(s)	Publication date
US 6578264	B1	17-06-2003	US	2003192183 A1	16-10-2003
US 2004201392	A1	14-10-2004	EP	1616197 A1	18-01-2006
			WO	2004092750 A1	28-10-2004
US 6441315	B1	27-08-2002	AU	1913000 A	29-05-2000
			CN	1497794 A	19-05-2004
			CN	1127781 C	12-11-2003
			DE	69927996 D1	01-12-2005
			EP	1129510 A1	05-09-2001
			JP	2002529903 T	10-09-2002
			JP	2004139992 A	13-05-2004
			TW	588483 B	21-05-2004
			WO	0028625 A1	18-05-2000
			US	2003015347 A1	23-01-2003
JP 2002040052	A	06-02-2002	NONE		
US 2004070417	A1	15-04-2004	JP	2004138393 A	13-05-2004
US 6208375	B1	27-03-2001	NONE		
US 2005001644	A1	06-01-2005	US	2005007130 A1	13-01-2005
			US	2005001641 A1	06-01-2005
			US	2005001642 A1	06-01-2005
			US	2005001643 A1	06-01-2005